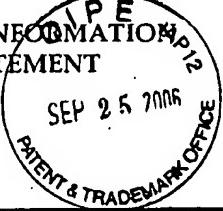


FORM PTO - 1449  <b>SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT</b>				ATTORNEY DOCKET NO.: ASC-022CPC1 APPLICANTS: Wu et al. SERIAL NO.: 10/603,852 FILING DATE: June 25, 2003 GROUP: 2811			
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	C167	International Search Report and Written Opinion from the International Examining Authority for related application PCT/US01/19613, dated June 22, 2002							
DWO	C168	Kuboto M., et al. "New SOI CMOS Process with Selective Oxidation," IEEE IEDM TECH, DIG., pp. 814-816 (1986)							
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